

<b>INFORMATION DISCLOSURE CITATION</b> PTO-1449		Customer Number <b>26615</b>	ATTORNEY'S DKT No. H1417D	DIVISIONAL APPLICATION OF APPLICATION SERIAL No. 10/405,343	
			APPLICANT(S) Ming-Ren Lin et al.		10/825175
			FILING DATE APRIL 16, 2004	GROUP <del>Unassigned</del> 2813	

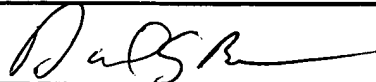
  

U.S. PATENT DOCUMENTS						
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
DS	6,645,797 B1	11-11-03	Buynoski et al.	438	157	12-06-02
	6,583,469 B1	06-24-03	Fried et al.	257	329	01-28-02
	6,562,665 B1	05-13-03	Yu	438	149	10-16-00
	6,537,880 B1	03-25-03	Tseng	438	260	09-13-01
	6,514,819 B1	02-04-03	Choi	438	253	02-26-99
	6,492,212 B1	12-10-02	leong et al.	438	157	10-05-01
	6,413,802 B1	07-02-02	Hu et al.	438	151	10-23-00
	6,358,827 B1	03-19-02	Chen et al.	438	585	01-19-01
	6,232,622 B1	05-15-01	Hamada	257	67	09-28-99
	6,180,441 B1	01-30-01	Yue et al.	438	197	05-10-99
	5,932,911	08-03-99	Yue et al.	257	330	12-13-96
✓	5,705,414	01-06-98	Lustig	437	41	12-23-96

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)	
DS	Digh Hisamoto et al., "FinFET-A Self-Aligned Double-Gate MOSFET Scalable to 20 nm," IEEE Transactions on Electron Devices, Vol. 47, No. 12, December 2000, pages 2320-2325.
	Yang-Kyu Choi et al., "Sub-20nm CMOS FinFET Technologies," 2001 IEEE, IEDM, pages 421-424.
	Xuejue Huang et al., "Sub-50 nm P-Channel FinFET," IEEE Transactions on Electron Devices, Vol. 48, No. 5, May 2001, pages 880-886.
	Xuejue Huang et al., "Sub 50-nm FinFET: PMOS," 1999 IEEE, IEDM, pages 67-70.
	Yang-Kyu Choi et al., "Nanoscale CMOS Spacer FinFET for the Terabit Era," IEEE Electron Device Letters, Vol. 23, No. 1, January 2002, pages 25-27.
✓	Co-pending U.S. Patent Application Serial No. 10/726,569, filed December 4, 2003, titled "SYSTEMS AND METHODS FOR FORMING MULTIPLE FIN STRUCTURES USING METAL-INDUCED-CRYSTALLIZATION," 23 pages.

EXAMINER	DATE CONSIDERED
	9/27/04

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant(s).

